Novel Logic and Memory Devices in Graphene Sanjay Banerjee

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V_{TI} (V)

Advances in graphene growth and device processing have enabled a host of advanced device concepts. We will describe field effect transistors (FETs) and beyond-CMOS ideas such as tunnel FETs which show negative differential resistance (NDR) that are enabled by the unique properties of graphene [1-2]. We will discuss applications of such devices in memory and logic circuits. Challenges in large scale integration of such devices and commercialization will be discussed.

15 (NA) 10 Inter-Layer Current I_{IL} 5 0 -5 -10 -40 V 0 V -15 40 V -20 -0.5 0 -1 0.5 1 Inter-Layer Bias V_{TL} (V)

References:

1. B. Fallahazad, K. Lee, S. Kang, L. Register, S. Banerjee and E. Tutuc, Nano Letters (15) Issue: 1 (2015) Pg: 428-433

2. S. Kang, B. Fallahazad, K. Lee, H. Movva, K. Kim, L. Colombo, L. Register, E. Tutuc, S. Banerjee, IEEE

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Figure 2: Use of NDR in 1-transistor static random access memory circuit. Conventional CMOS SRAMs require 4 transistors.

Figure 1: Bi-layer graphene-hBN tunnel FET showing negative differential resistance (NDR).

V_{DD} (V)